

PATENT APPLICATION

**RESPONSE UNDER 37 CFR §1.116
EXPEDITED PROCEDURE
TECHNOLOGY CENTER ART UNIT 1763**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Kazuo ICHIKAWA et al.

Group Art Unit: 1763

Application No.: 09/670,877

Examiner: R. Zervigon

Filed: September 27, 2000

Docket No.: 107469

For: CVD SUBSTRATE AND CLEANING METHOD

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TECHNOLOGY CENTER 1763

DEC - 6 2002

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AMENDMENT AFTER FINAL REJECTION UNDER 37 CFR §1.116

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the August 6, 2002 Office Action, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claims 1 and 3 as follows:

1. (Amended) A CVD system provided with a plasma generator having a plasma generation chamber separated from a film deposition chamber in which a substrate is arranged, wherein a material gas is directly supplied into the film deposition chamber, radicals in the plasma are introduced into the film deposition chamber from the plasma generator through introduction holes of a lower plate, and a thin film is deposited on the substrate, said CVD system further comprising:

a cleaning gas feeder provided to said plasma generator,

said lower plate is connected to ground, and

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